

Fabrication of antireflective SiC surface using plasma etching with self-assembled nanopattern - DTU Orbit (09/11/2017)

Fabrication of antireflective SiC surface using plasma etching with self-assembled nanopattern

General information

State: Published

Organisations: Department of Photonics Engineering, Department of Micro- and Nanotechnology, Nanoprobes, Diode Lasers and LED Systems

Authors: Ou, Y. (Intern), Argyraki, A. (Intern), Ou, H. (Intern)

Publication date: 2013

Event: Poster session presented at 39th International Conference on Micro and Nano Engineering, London, United Kingdom.

Main Research Area: Technical/natural sciences

Electronic versions:

2013 MNE A0.ppt

Bibliographical note

39th International Conference on Micro and Nano Engineering
16 – 19 September 2013

Relations

Activities:

39th International Conference on Micro and Nano Engineering

Source: dtu

Source-ID: u::8778

Publication: Research - peer-review › Poster – Annual report year: 2013